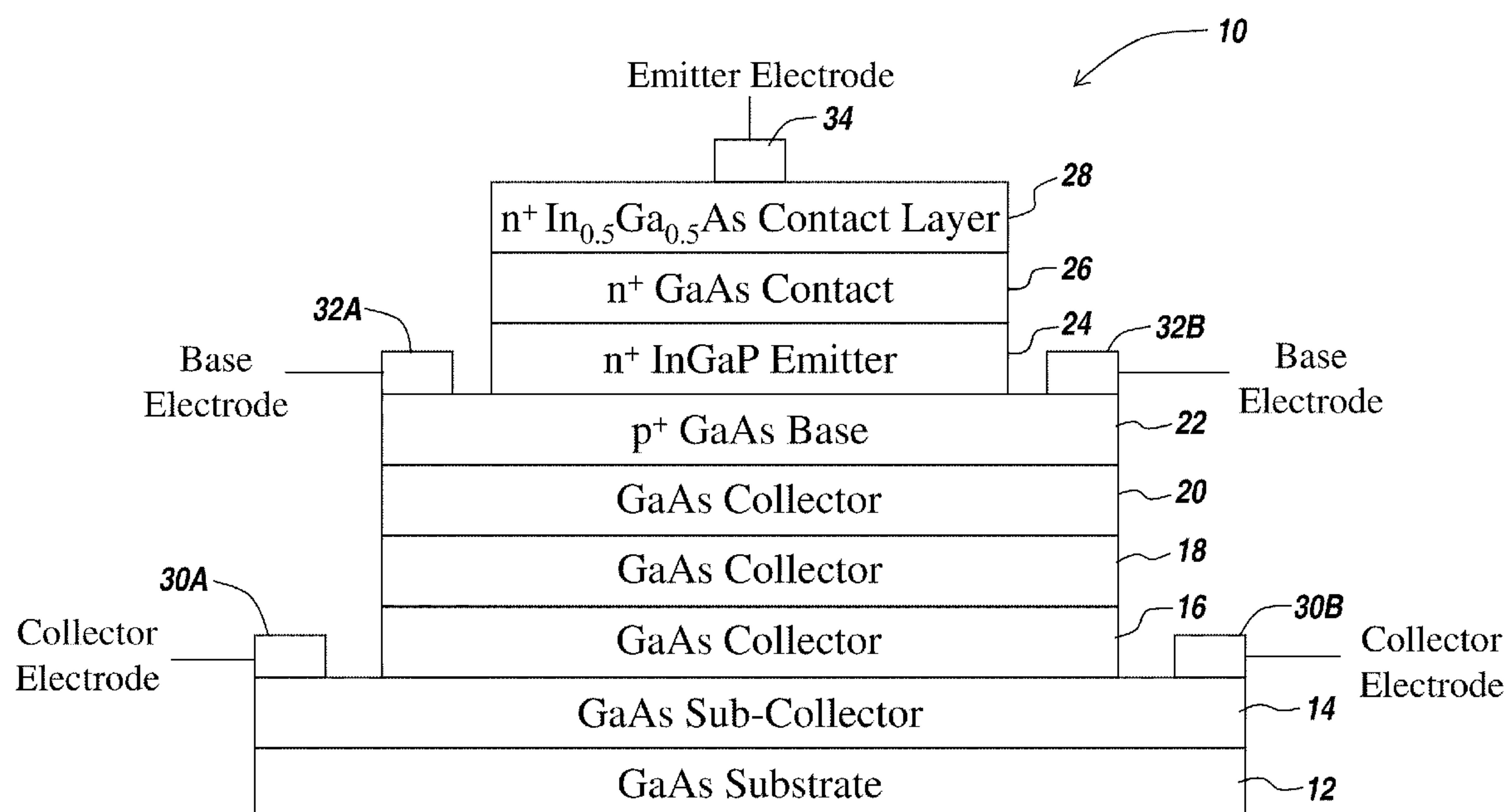


US 20100237388A1

(19) **United States**(12) **Patent Application Publication**
PAN et al.(10) **Pub. No.: US 2010/0237388 A1**(43) **Pub. Date: Sep. 23, 2010**(54) **HIGH ON-STATE BREAKDOWN
HETEROJUNCTION BIPOLAR TRANSISTOR**(60) Provisional application No. 60/603,011, filed on Aug.
19, 2004.(75) Inventors: **Noren PAN**, Wilmette, IL (US);
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(US)**Publication Classification**(51) **Int. Cl.**
H01L 29/737 (2006.01)(52) **U.S. Cl. ... 257/197; 257/487; 257/565; 257/E29.188**Correspondence Address:
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(US)(21) Appl. No.: **12/731,719**(22) Filed: **Mar. 25, 2010****Related U.S. Application Data**(62) Division of application No. 11/153,078, filed on Jun.
14, 2005, now Pat. No. 7,687,886.(57) **ABSTRACT**

A heterojunction bipolar transistor (HBT) is provided with an improved on-state breakdown voltage V_{CE} . The improvement of the on-state breakdown voltage for the HBT improves the output power characteristics of the HBT and the ability of the HBT to withstand large impedance mismatch (large VSWR). The improvement in the on-state breakdown voltage is related to the suppression of high electric fields adjacent a junction of a collector layer and a sub-collector layer forming a collector region of the HBT.



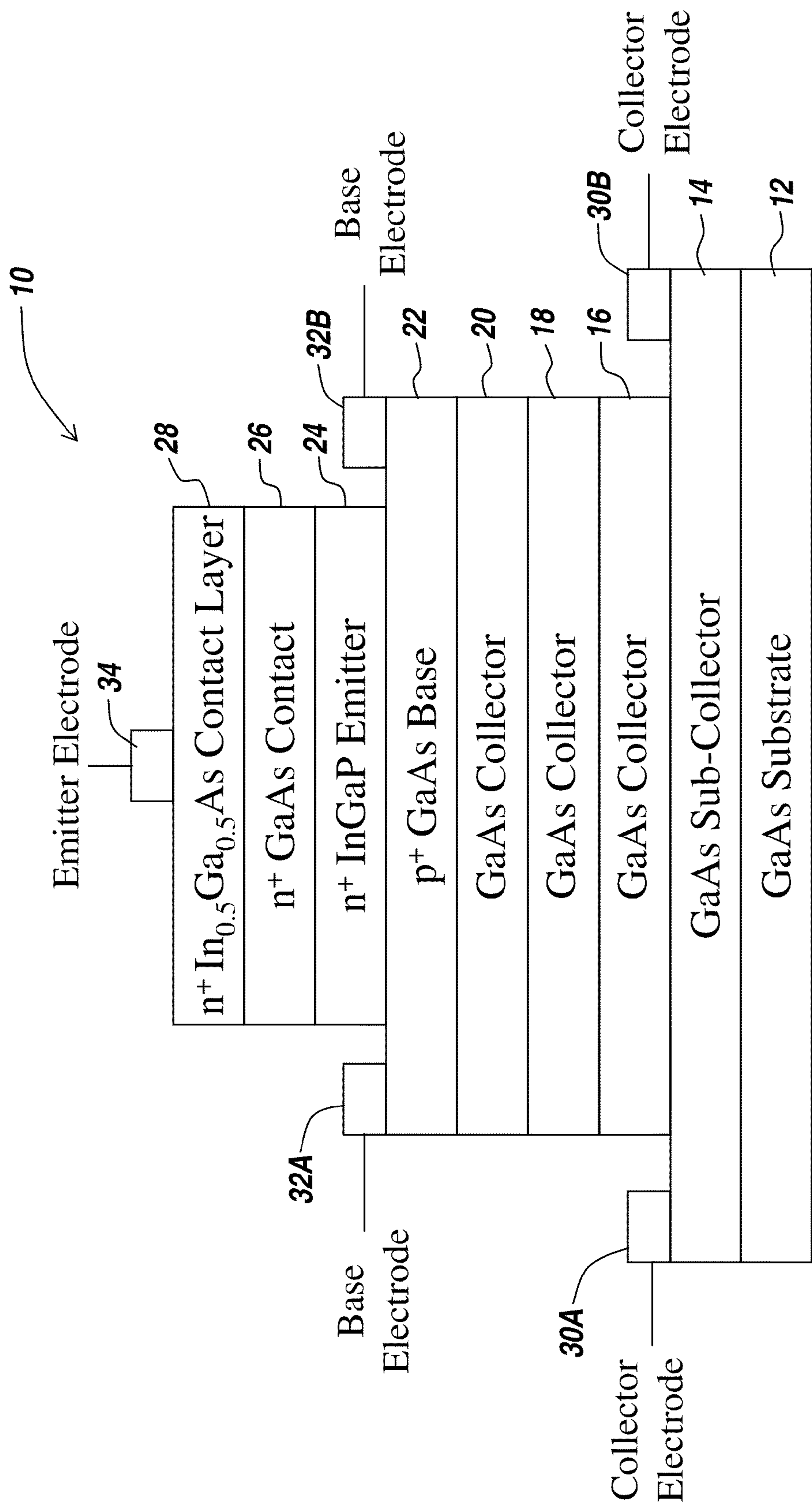


Fig. 1

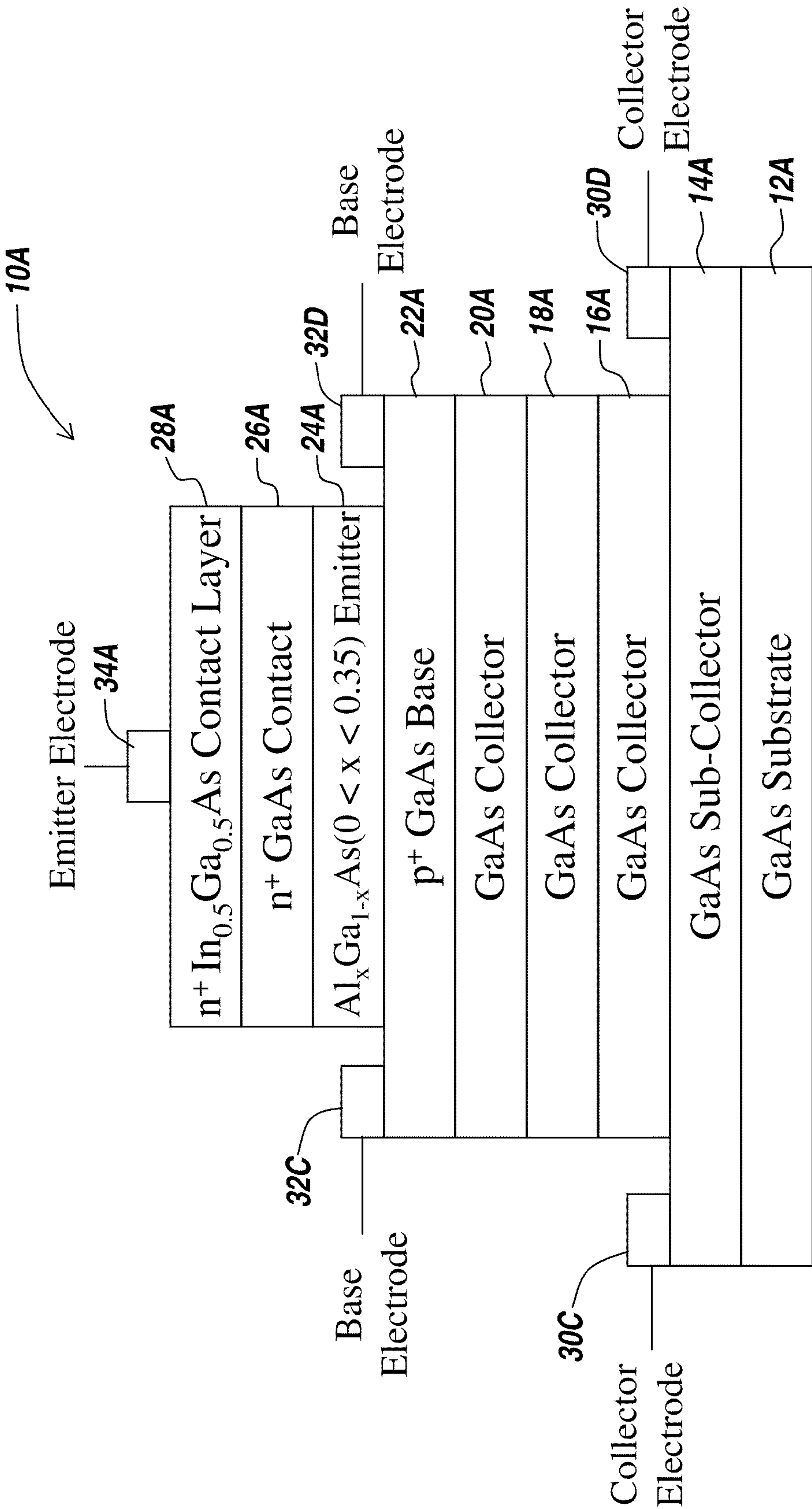


Fig. 1A

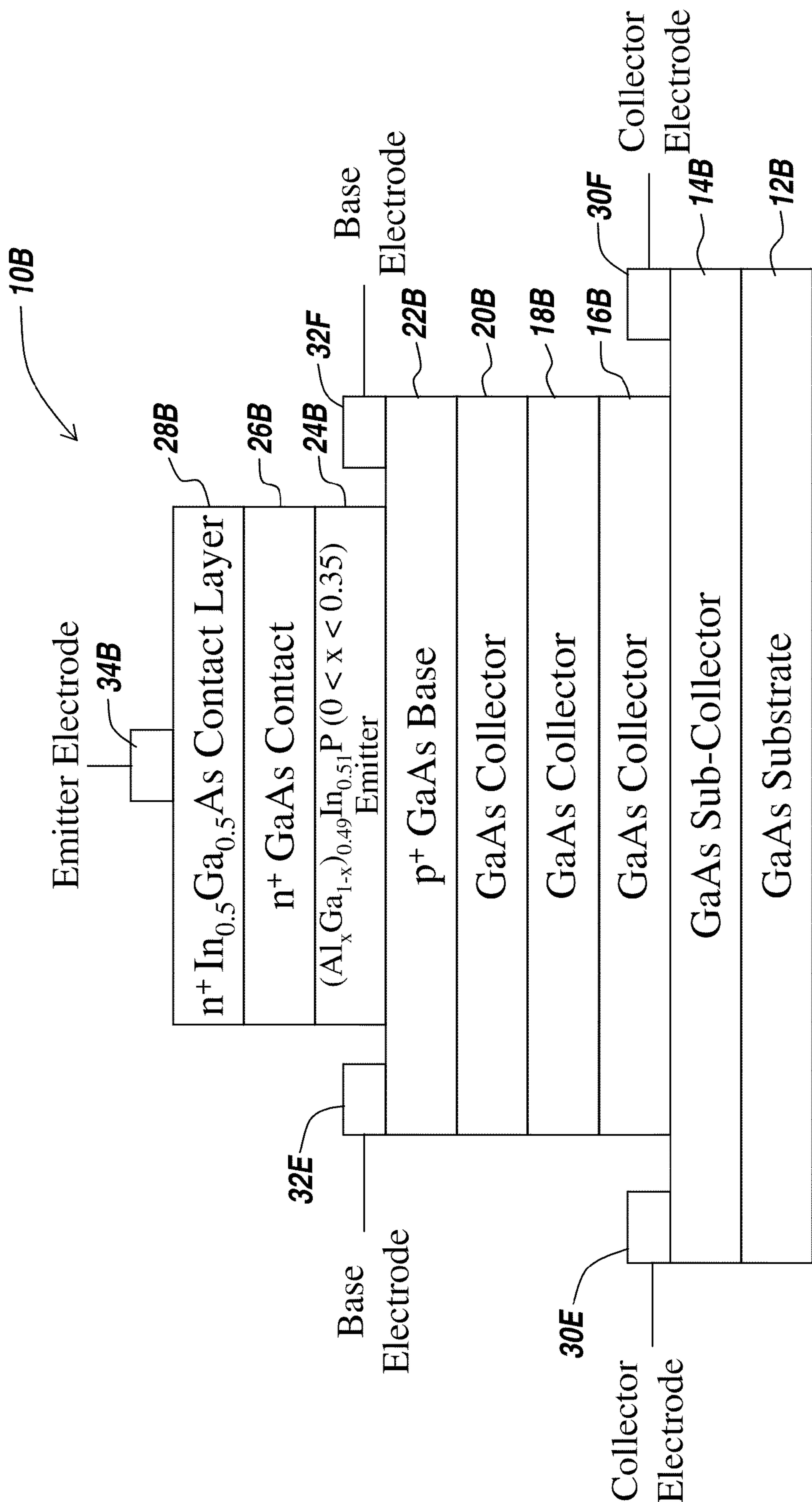


Fig. 1B

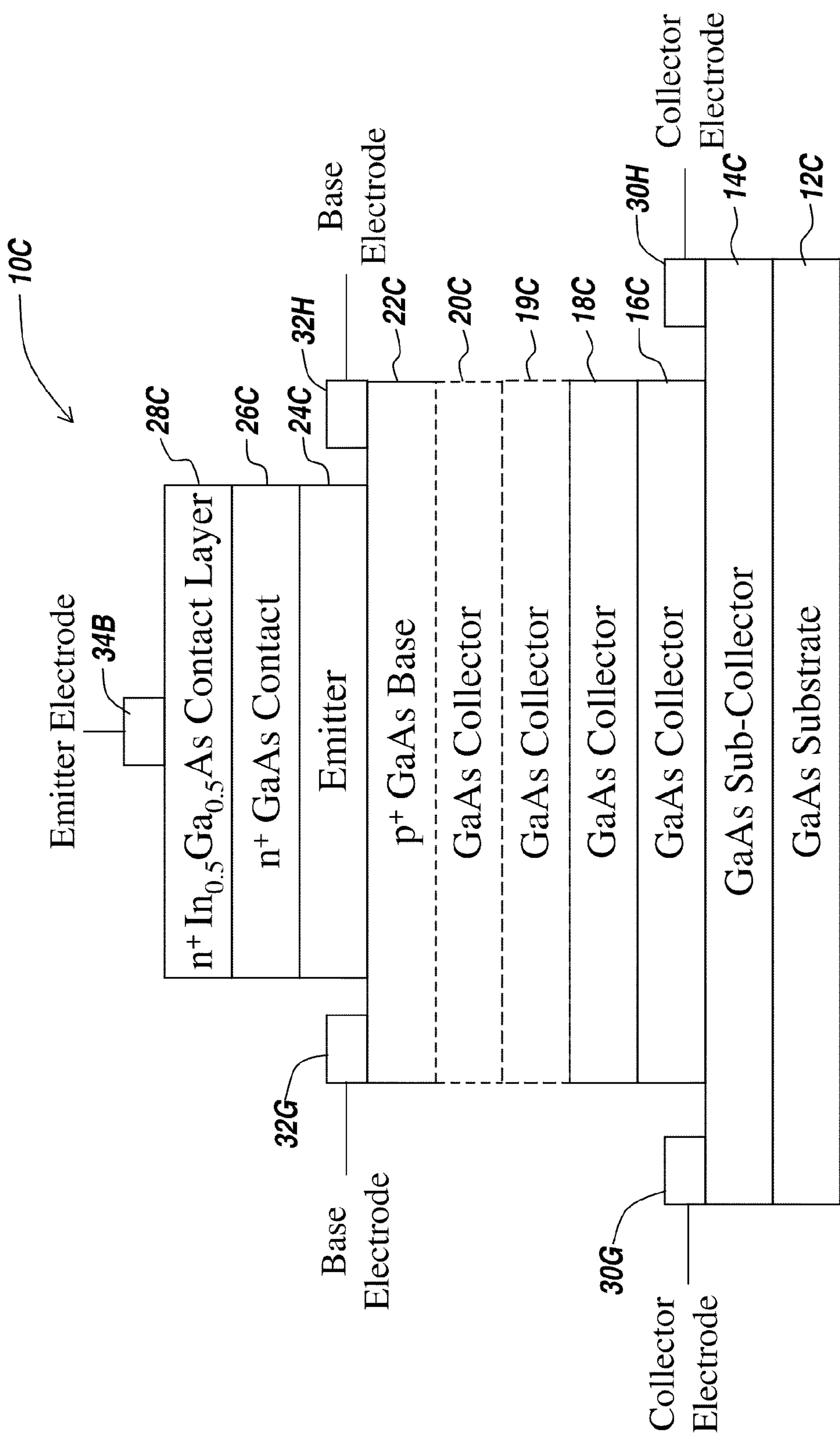


Fig. 1C

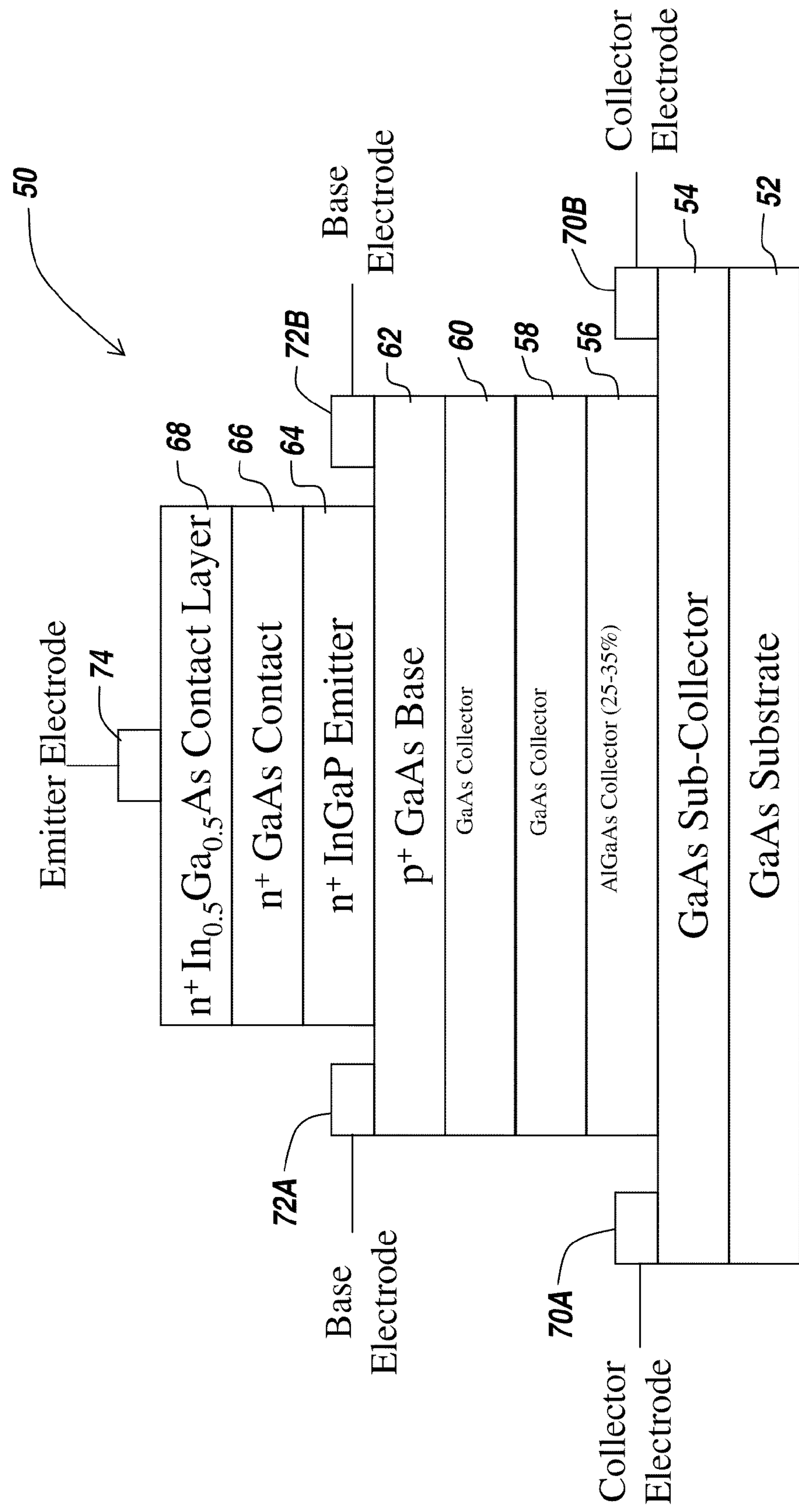


Fig. 2

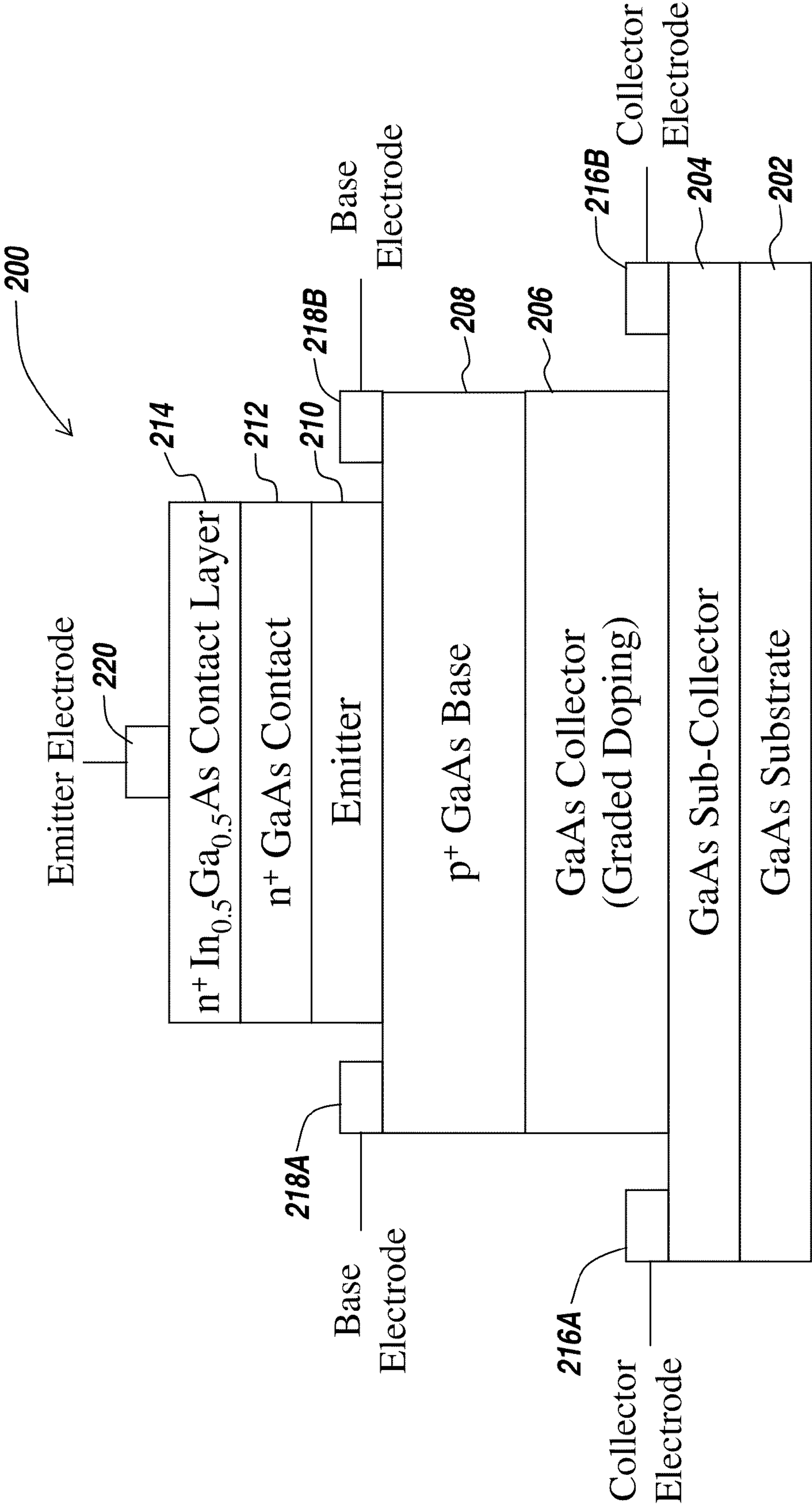


Fig. 3

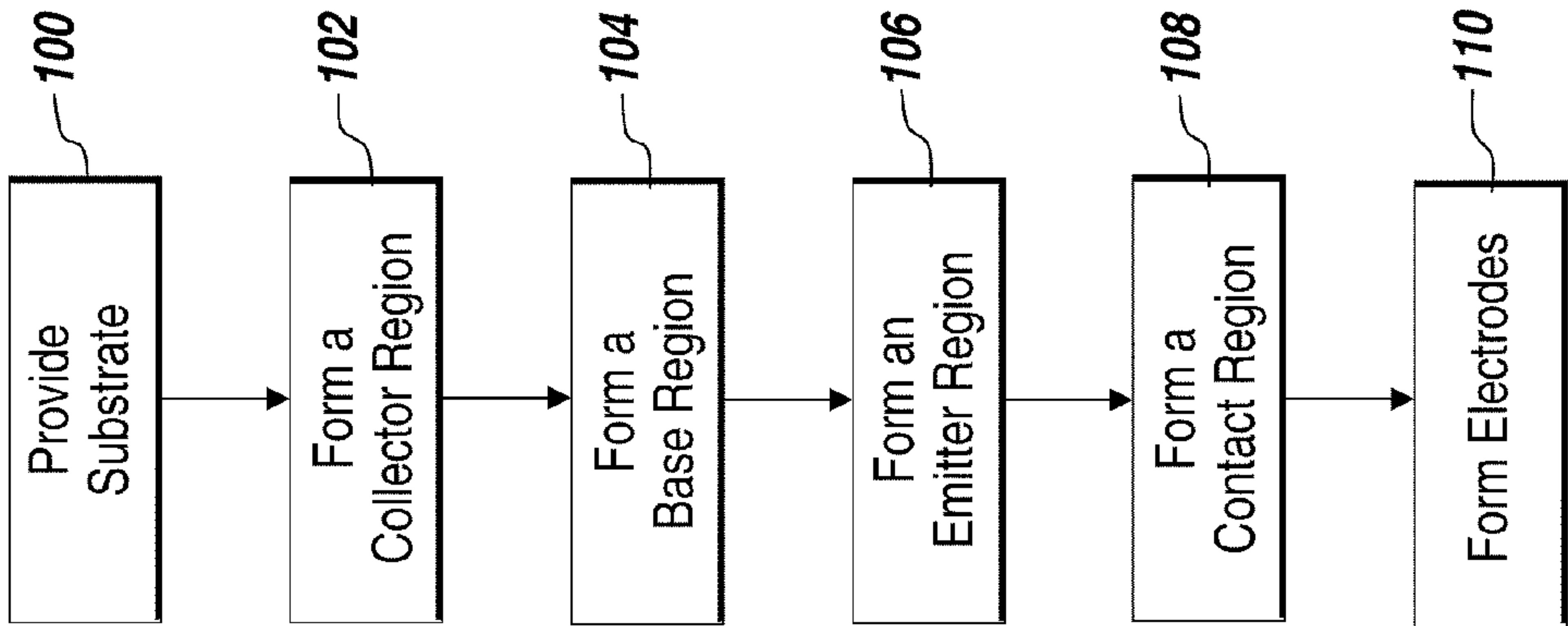


Fig. 4

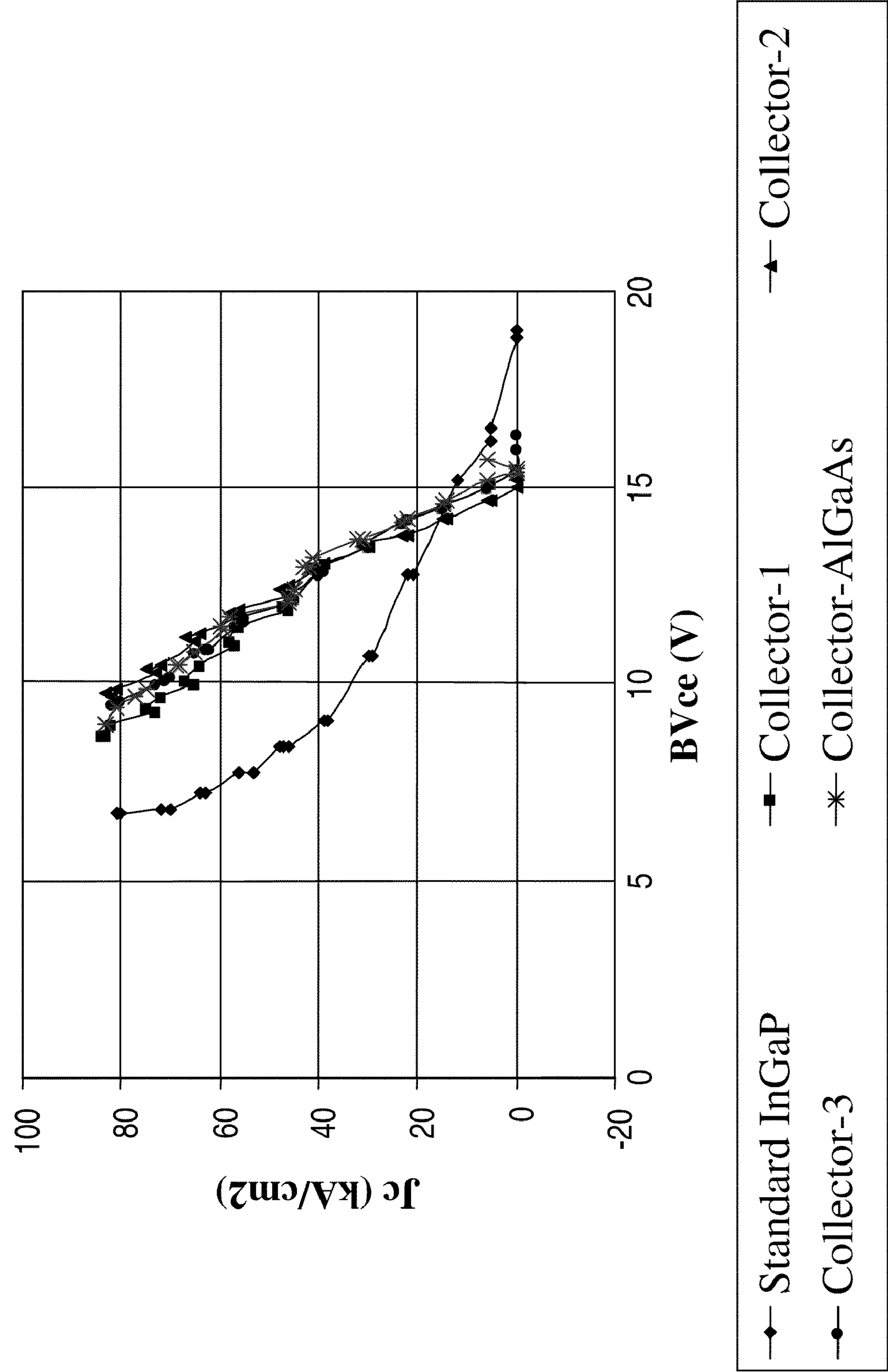


Fig. 5

HIGH ON-STATE BREAKDOWN HETEROJUNCTION BIPOLAR TRANSISTOR

RELATED APPLICATIONS

[0001] The present invention is a divisional application of U.S. patent application Ser. No. 11/153,078, filed Jun. 14, 2005, which claims priority to U.S. Provisional Application Ser. No. 60/603,011, filed Aug. 19, 2004, the entire content of each application is herein incorporated by reference in their entirety.

BACKGROUND OF THE INVENTION

[0002] This invention relates generally to semiconductor transistors. In particular, the invention relates to heterojunction bipolar transistors. Heterojunction bipolar transistors (HBTs) offer a much higher speed of operation than the more prevalent metal oxide semiconductor field effect transistors (MOSFETs) or even conventional homojunction bipolar transistors, e.g., pnp or npn silicon transistors. Because HBTs offer high speed, high current driving capability, and low 1/f noise levels, HBTs are becoming popular for use as integrated switching devices and power amplifier devices in wireless communication systems and subsystems, satellite broadcast systems, automobile collision avoidance systems, global positioning systems, and other high frequency applications. One application in which HBT use continues to increase is in the design and manufacture of wireless electronic devices, such as wireless telephones and other like electronic devices that are capable of communicating with a network in a wireless manner.

[0003] As with all wireless electronic devices, the output power characteristics of a power amplifier along with the amplifier's ability to withstand large voltage swings is a concern to both the designer and consumer of the portable wireless device. For example, it is desirable to maximize output power and reliability of the wireless electronic device by providing the device with one or more HBT power amplifiers that maximize power performance and high frequency performance and thus, broad bandwidth operation capability. By providing the wireless electronic device with an HBT power amplifier having an improved on-state breakdown capability often results in a desirable increase in the reliability of the amplifier by improving the ability of the amplifier to withstand large voltage swings. As such, the use of an HBT power amplifier having an improved on-state breakdown capability improves output power characteristics and the ruggedness or the ability of the amplifier to withstand large voltage swings benefits a mobile telephone supporting a digital wireless telephone standard, such as the global system for mobile communication (GSM). Moreover, it is desirable to increase the reliability of an HBT power amplifier provided in a wireless electronic device by lowering the intensity of electric fields within a selected region of the HBT power amplifier.

SUMMARY OF THE INVENTION

[0004] The present invention addresses the above-described problems associated with electronic devices that transmit digital wireless communications. The present invention discloses structures for GaAs HBT power amplifiers having an improved on-state breakdown voltage (V_{CE}) and thus, improved output power characteristics and improved ability to withstand large voltage swings, amongst other benefits. The improvements provided in an HBT device are

accomplished by suppression of high electric fields near the collector/sub-collector junction when the HBT device is operating at high current densities and high voltage operations. By insertion of a high doping level layer near the collector/sub-collector junction or by insertion of a large bandgap material the present invention suppresses the high electric fields near the collector/sub-collector junction to result in an HBT device having an improved on-state breakdown voltage value.

[0005] In one embodiment of the present invention, a heterojunction bipolar transistor is disclosed having a collector region configured to reduce an electric field adjacent to two of the layers forming the region to improve a drain source on-state breakdown voltage. The heterojunction bipolar transistor includes a substrate, a collector region, a base region, an emitter region, and a contact region. The collector region includes a number of layers of a first material. Each of the layers of the first material has a distinct impurity concentration. The base region has at least one layer of the first material. The emitter region has at least one layer of a second material and the contact region has a first layer of the first material and a second layer of a third material.

[0006] The collector region includes a sub-collector layer of the first material, a first collector layer of the first material, a second collector layer of the first material, and a third collector layer of the first material. The first material includes GaAs.

[0007] The first collector layer has a thickness of about 200 nm and a donor impurity concentration of between about $7 \times 10^{16} \text{ cm}^{-3}$ and about $10 \times 10^{16} \text{ cm}^{-3}$. The second collector layer has a thickness of about 200 nm. The third collector layer has a thickness of about 400 nm.

[0008] The second material includes InGaP and the third material includes $\text{In}_{0.5}\text{Ga}_{0.5}\text{As}$.

[0009] In one embodiment of the present invention, a heterojunction bipolar transistor is disclosed having a collector region configured to reduce an electric field adjacent to two of the layers forming the region to improve a drain source on-state breakdown voltage. The heterojunction bipolar transistor includes a substrate, a collector region, a base region, an emitter region, and a contact region. The collector region includes a number of layers of a first material. Each of the layers of the first material has a distinct impurity concentration. The base region has at least one layer of the first material. The emitter region has at least one layer of a second material and the contact region has a first layer of the first material and a second layer of a third material.

[0010] The collector region includes a sub-collector layer of the first material, a first collector layer of the first material, a second collector layer of the first material, and a third collector layer of the first material. The first material includes GaAs.

[0011] The first collector layer has a thickness of about 200 nm and a donor impurity concentration of between about $7 \times 10^{16} \text{ cm}^{-3}$ and about $10 \times 10^{16} \text{ cm}^{-3}$. The second collector layer has a thickness of about 200 nm. The third collector layer has a thickness of about 400 nm.

[0012] The second material includes $\text{Al}_x\text{Ga}_{1-x}\text{As}$ ($0 < x < 0.35$) and the third material includes $\text{In}_{0.5}\text{Ga}_{0.5}\text{As}$.

[0013] In another embodiment of the present invention, a heterojunction bipolar transistor is disclosed having a collector region configured to reduce an electric field adjacent to two of the layers forming the region to improve a drain source on-state breakdown voltage. The heterojunction bipolar tran-

sistor includes a substrate, a collector region, a base region, an emitter region, and a contact region. The collector region includes a number of layers of a first material. Each of the layers of the first material has a distinct impurity concentration. The base region has at least one layer of the first material. The emitter region has at least one layer of a second material and the contact region has a first layer of the first material and a second layer of a third material.

[0014] The collector region includes a sub-collector layer of the first material, a first collector layer of the first material, a second collector layer of the first material, and a third collector layer of the first material. The first material includes GaAs.

[0015] The first collector layer has a thickness of about 200 nm and a donor impurity concentration of between about $7 \times 10^{16} \text{ cm}^{-3}$ and about $10 \times 10^{16} \text{ cm}^{-3}$. The second collector layer has a thickness of about 200 nm. The third collector layer has a thickness of about 400 nm.

[0016] The second material includes $(\text{Al}_x\text{Ga}_{1-x})_{0.49}\text{In}_{0.51}\text{P}$ ($0 < x < 0.35$) and the third material includes $\text{In}_{0.5}\text{Ga}_{0.5}\text{As}$.

[0017] In another embodiment of the present invention, a heterojunction bipolar transistor is disclosed having a collector region configured to reduce an electric field adjacent to two adjacent layers of a number of layers forming the collector region. The reduction in the electric field improves a drain-source on-state breakdown voltage of the heterojunction bipolar transistor. The heterojunction bipolar transistor includes a substrate, a collector region, a base region, an emitter region, and a contact region.

[0018] The collector region includes a number of layers of a first material and a layer of a second material. Each of the layers of the first and second materials has a distinct impurity concentration. The base region includes at least one layer of the first material. The emitter region includes at least one layer of a third material. The contact region includes a first layer of the first material and a second layer of a fourth material.

[0019] The first material includes GaAs. The second material includes AlGaAs. The third material includes InGaP. The fourth material includes $\text{In}_{0.5}\text{Ga}_{0.5}\text{As}$.

[0020] The layers of the first material forming the collector region include a sub-collector layer of the first material, a first collector layer of the first material, and a second collector layer of the first material.

[0021] The first collector layer of the first material has a thickness of about 200 nm. The second collector layer of the first material has a thickness of about 400 nm. The sub-collector layer has a thickness of about 400 nm. The layer of the second material forming the collector region has a thickness of about 200 nm and has a donor impurity concentration of between about $7 \times 10^{16} \text{ cm}^{-3}$ and about $10 \times 10^{16} \text{ cm}^{-3}$.

BRIEF DESCRIPTION OF THE DRAWINGS

[0022] The foregoing and other objects, features and advantages of the invention will be apparent from the following description, and from the accompanying drawings, in which like reference characters refer to the same parts throughout the different views. The drawings illustrate principles of the invention and are not to scale.

[0023] FIG. 1 is a cross-sectional view of a heterojunction bipolar transistor according to a first illustrative embodiment of the present invention.

[0024] FIG. 1A is a cross-sectional view of a heterojunction bipolar transistor according to a second illustrative embodiment of the present invention.

[0025] FIG. 1B is a cross-sectional view of a heterojunction bipolar transistor according to a third illustrative embodiment of the present invention.

[0026] FIG. 1C is a cross-sectional view of a heterojunction bipolar transistor according to a fourth illustrative embodiment of the present invention.

[0027] FIG. 2 is a cross-sectional view of a heterojunction bipolar transistor according to a fifth illustrative embodiment of the present invention.

[0028] FIG. 3 is a cross-sectional view of a heterojunction bipolar transistor according to a sixth illustrative embodiment of the present invention.

[0029] FIG. 4 is a schematic flow-chart diagram illustrating a method for fabricating either of heterojunction bipolar transistors illustrated in FIGS. 1, 1A, 1B, 1C, 2, and 3.

[0030] FIG. 5 is a graph representing improved on state voltage breakdown of heterojunction bipolar transistors according to the teachings of the present invention.

DETAILED DESCRIPTION

[0031] The compound semiconductor device of the present invention advantageously employs either a highly doped layer near the collector/sub-collector junction of the device or a layer of material near the collector/sub-collector junction of the device having a large bandgap to allow the compound semiconductor device to realize an improved V_{CE} . The improved V_{CE} realized by the semiconductor device of the present invention improves the output power characteristics of the device along with the ability of the device to withstand large voltage mismatch (high VSWR) (Voltage Standing Wave Ratio). Those skilled in the art will appreciate that an impedance mismatch of a power amplifier can be very high (e.g., $\text{VSWR} > 10$) when the power amplifier undergoes significant changes in operation. Nonetheless, the teachings of the present invention, discloses an HBT structure suitable to provide a power amplifier capable of operating under conditions of $\text{VSWR} > 15$ and a V_{CE} greater than 5V.

[0032] The improved on-state breakdown voltage V_{CE} results from the suppression or reduction of high electric fields near the collector/sub-collector junction of the compound semiconductor device. That is, the electric field at the collector/sub collector junction is reduced to less than $2 \times 10^4 \text{ V/cm}$.

[0033] The compound semiconductor devices of the present invention are particularly suitable for use in applications where the compound semiconductor device operates as a power amplifier and are fabricated from a GaAs material. Specifically, each illustrative embodiment of the present invention described below is directed to a GaAs based HBT device for use in a portable or a mobile electronic device, such as a cellular telephone, a laptop computer with wireless modem and other like portable consumer or non-consumer (e.g., military) device or other like or similar wireless communication application that supports transmission of digital data. For example, one such portable device is a mobile telephone configured to digitize and compress data, and transmit the data in wireless fashion across a channel with other streams of digitized compressed data, each in its own time slot. The compound semiconductor device of the present

invention is configurable to suit a selected application as illustrated in the exemplary embodiments described in more detail below.

[0034] The compound semiconductor device of the present invention provides a range of significant benefits to engineers that design electronic devices that are capable of transmitting data in a GSM compatible network for wireless communications. The compound semiconductor device of the present invention can extend or improve the on-state breakdown voltage of the device to improve the output power characteristics of the device and the ability of the device to withstand large voltage swings. The compound semiconductor device of the present invention is able to extend or improve on-state breakdown voltage of a GaAs HBT by suppressing or reducing the strength of electric fields produced near the junction of a collector layer and a sub-collector layer of the HBT device when the device is operating at high current densities and high voltage operations. For example, the improvement in the on-state breakdown can be realized at current densities from 20 kA/cm² to 100 kA/cm² and at V_{CE} from 5V to 16V. In this manner, the GaAs HBTs of the present invention are well suited for applications that transmit compressed digitized data in a wireless manner.

[0035] FIG. 1 illustrates a cross sectional view of an HBT according to a first illustrative embodiment of the present invention. The HBT 10 is formed on a substrate and includes a collector region, a base region, an emitter region, and a contact region. The collector region of the HBT 10 includes a sub-collector layer 14, a first collector layer 16, a second collector layer 18, and a third collector layer 20. The base region of the HBT 10 includes a base layer 22. In similar fashion, the emitter region of the HBT 10 includes an emitter layer 24. The contact region of the HBT 10 includes a first contact layer 26 and a second contact layer 28. The HBT 10 further includes an emitter electrode 34 formed over a portion of the second contact layer 28, base electrodes 32A and 32B formed over portions of the base layer 22, and collector electrodes 30A and 30B formed over portions of the sub-collector layer 14.

[0036] In more detail, the sub-collector layer 14 is a GaAs material formed over a GaAs substrate 12. The sub-collector layer 14 has a thickness of about 400 nm with a donor impurity concentration of about $4 \times 10^{18} \text{ cm}^{-3}$.

[0037] The first collector layer 16 is formed of a GaAs material over a portion of the sub-collector layer 14. The first collector layer 16 can have a thickness range of between about 200 nm and about 400 nm. The first collector layer 16 can have a donor impurity concentration of between about $7 \times 10^{16} \text{ cm}^{-3}$ and about $10 \times 10^{16} \text{ cm}^{-3}$. In one embodiment the first collector layer 16 has a thickness of about 200 nm and a donor impurity concentration of about $7 \times 10^{16} \text{ cm}^{-3}$.

[0038] The second collector layer 18 is formed of a GaAs material over a portion of the first collector layer 16. The second collector layer 18 has a thickness that can range from between about 200 nm to about 400 nm in 1 nm increments or decrements. The donor impurity concentration of the second collector layer 18 can range between about $4 \times 10^{16} \text{ cm}^{-3}$ and about $7 \times 10^{16} \text{ cm}^{-3}$. In one embodiment, the second collector layer 18 has a thickness of about 200 nm and a donor impurity concentration of about $5 \times 10^{16} \text{ cm}^{-3}$.

[0039] The third collector layer 20 is formed of a GaAs material over a portion of the second collector layer 18. The third collector layer 20 has a thickness of between about 100 nm and about 500 nm. The range of thicknesses can change in

increments or decrements of 1 nm. The donor impurity concentration of the third collector layer 20 can range between about $0.5 \times 10^{16} \text{ cm}^{-3}$ and about $4 \times 10^{16} \text{ cm}^{-3}$. In one embodiment, the third collector layer 20 has a thickness of about 400 nm and a donor impurity concentration of about $1 \times 10^{16} \text{ cm}^{-3}$.

[0040] For the base layer 22, a P⁺ type GaAs material is formed over a portion of the third collector layer 20 and is formed to have a thickness of about 100 nm. The base layer 22 is doped to have an impurity concentration of between about $1 \times 10^{19} \text{ cm}^{-3}$ and about $5 \times 10^{19} \text{ cm}^{-3}$.

[0041] For the emitter layer 24, an N⁺ type InGaP material is formed over a portion of the base layer 22 to a thickness of about 50 nm with a donor impurity concentration of about $3 \times 10^{17} \text{ cm}^{-3}$.

[0042] The first contact layer 26 is formed of a GaAs material doped with N⁺ type impurities to a concentration of about $4 \times 10^{18} \text{ cm}^{-3}$. The first contact layer 26 is formed over a portion of the emitter layer 24 and is formed to have a thickness of about 100 nm. The second contact layer 28 is formed over a portion of the first contact layer 26 of an In_{0.5}Ga_{0.5}As material doped with N⁺ type impurities in a concentration above $1 \times 10^{19} \text{ cm}^{-3}$.

[0043] The improvement in the on-state voltage breakdown V_{CE} in the above illustrative embodiment of the compound semiconductor device is accomplished by the insertion of a higher doped collector layer near the sub-collector layer to reduce the electric field at the junction of the collector and the sub-collector of the HBT 10. The introduction of collector layer having a donor impurity concentration of between about $7 \times 10^{16} \text{ cm}^{-3}$ and about $10 \times 10^{16} \text{ cm}^{-3}$ adjacent to a sub-collector layer reduces the electric field at the collector/sub-collector junction which avoids the occurrence of avalanche breakdown at this junction.

[0044] The electric field at the junction of a sub-collector layer and a collector layer is reduced from between about $6 \times 10^4 \text{ V/cm}$ to about $8 \times 10^4 \text{ V/cm}$ to a reduced level of between about $2 \times 10^4 \text{ V/cm}$ to about $3 \times 10^4 \text{ V/cm}$. The reduction in the electric field results in an improvement of an on-state breakdown voltage V_{CE} value of between about 9V and about 10V at a collector current density of about 80 kA/cm². As a result, the HBT 10 is able to realize an improvement in on-state breakdown voltage V_{CE} , thus improved output power characteristics and the ability to withstand large voltage swings to result in an improvement in device reliability and operational performance.

[0045] FIG. 1A illustrates a cross sectional view of an HBT according to a second illustrative embodiment of the present invention. The HBT 10A is formed on a substrate and includes a collector region, a base region, an emitter region, and a contact region. The collector region of the HBT 10A includes a sub-collector layer 14A, a first collector layer 16A, a second collector layer 18A, and a third collector layer 20A. The base region of the HBT 10A includes a base layer 22A. In similar fashion, the emitter region of the HBT 10A includes an emitter layer 24A. The contact region of the HBT 10A includes a first contact layer 26A and a second contact layer 28A. The HBT 10A further includes an emitter electrode 34A formed over a portion of the second contact layer 28A, base electrodes 32C and 32D formed over portions of the base layer 22A, and collector electrodes 30C and 30D formed over portions of the sub-collector layer 14A.

[0046] In more detail, the sub-collector layer 14A is a GaAs material formed over a GaAs substrate 12A. The sub-collec-

tor layer **14A** has a thickness of about 400 nm with a donor impurity concentration of about $4 \times 10^{18} \text{ cm}^{-3}$.

[0047] The first collector layer **16A** is formed of a GaAs material over a portion of the sub-collector layer **14A**. The first collector layer **16A** can have a thickness range of between about 200 nm and about 400 nm. The first collector layer **16A** can have a donor impurity concentration of between about $7 \times 10^{16} \text{ cm}^{-3}$ and about $10 \times 10^{16} \text{ cm}^{-3}$. In one embodiment, the first collector layer **16A** has a thickness of about 200 nm and a donor impurity concentration of about $7 \times 10^{16} \text{ cm}^{-3}$.

[0048] The second collector layer **18A** is formed of a GaAs material over a portion of the first collector layer **16A**. The second collector layer **18A** has a thickness that can range from between about 200 nm to about 400 nm in 1 nm increments or decrements. The donor impurity concentration of the second collector layer **18A** can range between about $4 \times 10^{16} \text{ cm}^{-3}$ and about $7 \times 10^{16} \text{ cm}^{-3}$. In one embodiment, the second collector layer **18A** has a thickness of about 200 nm and a donor impurity concentration of about $5 \times 10^{16} \text{ cm}^{-3}$.

[0049] The third collector layer **20A** is formed of a GaAs material over a portion of the second collector layer **18A**. The third collector layer **20A** has a thickness of between about 100 nm and about 500 nm. The range of thicknesses can change in increments or decrements of 1 nm. The donor impurity concentration of the third collector layer **20A** can range between about $0.5 \times 10^{16} \text{ cm}^{-3}$ and about $4 \times 10^{16} \text{ cm}^{-3}$. In one embodiment, the third collector layer **20A** has a thickness of about 400 nm and a donor impurity concentration of about $1 \times 10^{16} \text{ cm}^{-3}$.

[0050] For the base layer **22A**, a P^+ type GaAs material is formed over a portion of the third collector layer **20A** and is formed to have a thickness of about 100 nm. The base layer **22A** is doped to have an impurity concentration of between about $1 \times 10^{19} \text{ cm}^{-3}$ and about $5 \times 10^{19} \text{ cm}^{-3}$.

[0051] For the emitter layer **24A**, a $\text{Al}_x\text{Ga}_{1-x}\text{As}$ ($0 < x < 0.35$) type material is formed over a portion of the base layer **22A** to have a thickness of about 50 nm with a doping concentration between about $3 \times 10^{17} \text{ cm}^{-3}$ and about $10 \times 10^{17} \text{ cm}^{-3}$.

[0052] The first contact layer **26A** is formed of a GaAs material doped with N^+ type impurities to a concentration of about $4 \times 10^{18} \text{ cm}^{-3}$. The first contact layer **26A** is formed over a portion of the emitter layer **24A** and is formed to have a thickness of about 100 nm. The second contact layer **28A** is formed over a portion of the first contact layer **26A** of an $\text{In}_{0.5}\text{Ga}_{0.5}\text{As}$ material doped with N^+ type impurities in a concentration above $1 \times 10^{19} \text{ cm}^{-3}$.

[0053] The improvement in the on-state voltage breakdown V_{CE} in the above illustrative embodiment of the compound semiconductor device is accomplished by the insertion of a higher doped collector layer near the sub-collector layer to reduce the electric field at the junction of the collector and the sub-collector of the HBT **10A**. The introduction of collector layer having a donor impurity concentration of between about $7 \times 10^{16} \text{ cm}^{-3}$ and about $10 \times 10^{16} \text{ cm}^{-3}$ adjacent to a sub-collector layer reduces the electric field at the collector/sub-collector junction which avoids the occurrence of avalanche breakdown at this junction.

[0054] The electric field at the junction of a sub-collector layer and a collector layer is reduced from between about $6 \times 10^4 \text{ V/cm}$ to about $8 \times 10^4 \text{ V/cm}$ to a reduced level of between about $2 \times 10^4 \text{ V/cm}$ to about $3 \times 10^4 \text{ V/cm}$. The reduction in the electric field results in an improvement of an on-state breakdown voltage V_{CE} value of between about 9V

and about 10V at a collector current density of about 80 kA/cm^2 . As a result, the HBT **10A** is able to realize an improvement in on-state breakdown voltage V_{CE} , thus improved output power characteristics and the ability to withstand large voltage swings to result in an improvement in device reliability and operational performance.

[0055] FIG. 1B illustrates a cross sectional view of an HBT according to another illustrative embodiment of the present invention. The HBT **10B** is formed on a substrate and includes a collector region, a base region, an emitter region, and a contact region. The collector region of the HBT **10B** includes a sub-collector layer **14B**, a first collector layer **16B**, a second collector layer **18B**, and a third collector layer **20B**. The base region of the HBT **10B** includes a base layer **22B**. In similar fashion, the emitter region of the HBT **10B** includes an emitter layer **24B**. The contact region of the HBT **10B** includes a first contact layer **26B** and a second contact layer **28B**. The HBT **10B** further includes an emitter electrode **34B** formed over a portion of the second contact layer **28B**, base electrodes **32E** and **32F** formed over portions of the base layer **22B**, and collector electrodes **30E** and **30F** formed over portions of the sub-collector layer **14B**.

[0056] In more detail, the sub-collector layer **14B** is a GaAs material formed over a GaAs substrate **12B**. The sub-collector layer **14B** has a thickness of about 400 nm with a donor impurity concentration of about $4 \times 10^{18} \text{ cm}^{-3}$.

[0057] The first collector layer **16B** is formed of a GaAs material over a portion of the sub-collector layer **14B**. The first collector layer **16B** can have a thickness range of between about 200 nm and about 400 nm. The first collector layer **16B** can have a donor impurity concentration of between about $7 \times 10^{16} \text{ cm}^{-3}$ and about $10 \times 10^{16} \text{ cm}^{-3}$. In one embodiment, the first collector layer **16B** has a thickness of about 200 nm and a donor impurity concentration of about $7 \times 10^{16} \text{ cm}^{-3}$.

[0058] The second collector layer **18B** is formed of a GaAs material over a portion of the first collector layer **16B**. The second collector layer **18B** has a thickness that can range from between about 200 nm to about 400 nm in 1 nm increments or decrements. The donor impurity concentration of the second collector layer **18B** can range between about $4 \times 10^{16} \text{ cm}^{-3}$ and about $7 \times 10^{16} \text{ cm}^{-3}$. In one embodiment, the second collector layer **18B** has a thickness of about 200 nm and a donor impurity concentration of about $5 \times 10^{16} \text{ cm}^{-3}$.

[0059] The third collector layer **20B** is formed of a GaAs material over a portion of the second collector layer **18B**. The third collector layer **20B** has a thickness of between about 100 nm and about 500 nm. The range of thicknesses can change in increments or decrements of 1 nm. The donor impurity concentration of the third collector layer **20B** can range between about $0.84 \times 10^{16} \text{ cm}^{-3}$ and about $4 \times 10^{16} \text{ cm}^{-3}$. In one embodiment, the third collector layer **20B** has a thickness of about 400 nm and a donor impurity concentration of about $1 \times 10^{16} \text{ cm}^{-3}$.

[0060] For the base layer **22B**, a P^+ type GaAs material is formed over a portion of the third collector layer **20B** and is formed to have a thickness of about 100 nm. The base layer **22B** is doped to have an impurity concentration of between about $1 \times 10^{19} \text{ cm}^{-3}$ and about $5 \times 10^{19} \text{ cm}^{-3}$.

[0061] For the emitter layer **24B**, a $(\text{Al}_x\text{Ga}_{1-x})_{0.49}\text{In}_{0.51}\text{P}$ where ($0 < x < 0.35$) type material is formed over a portion of the base layer **22B** to have a thickness of about 50 nm with a doping concentration between about $3 \times 10^{17} \text{ cm}^{-3}$ and about $10 \times 10^{17} \text{ cm}^{-3}$.

[0062] The first contact layer **26B** is formed of a GaAs material doped with N^+ type impurities to a concentration of about $4 \times 10^{18} \text{ cm}^{-3}$. The first contact layer **26B** is formed over a portion of the emitter layer **24B** and is formed to have a thickness of about 100 nm. The second contact layer **28B** is formed over a portion of the first contact layer **26B** of an $\text{In}_{0.5}\text{Ga}_{0.5}\text{As}$ material doped with N^+ type impurities in a concentration above $1 \times 10^{19} \text{ cm}^{-3}$.

[0063] The improvement in the on-state voltage breakdown V_{CE} in the above illustrative embodiment of the compound semiconductor device is accomplished by the insertion of a higher doped collector layer near the sub-collector layer to reduce the electric field at the junction of the collector and the sub-collector of the HBT **10B**. The introduction of collector layer having a donor impurity concentration of between about $7 \times 10^{16} \text{ cm}^{-3}$ and about $10 \times 10^{16} \text{ cm}^{-3}$ adjacent to a sub-collector layer reduces the electric field at the collector/sub-collector junction which avoids the occurrence of avalanche breakdown at this junction.

[0064] The electric field at the junction of a sub-collector layer and a collector layer is reduced from between about $6 \times 10^4 \text{ V/cm}$ to about $8 \times 10^4 \text{ V/cm}$ to a reduced level of between about $2 \times 10^4 \text{ V/cm}$ to about $3 \times 10^4 \text{ V/cm}$. The reduction in the electric field results in an improvement of an on-state breakdown voltage V_{CE} value of between about 9V and about 10V at a collector current density of about 80 kA/cm^2 . As a result, the HBT **10B** is able to realize an improvement in on-state breakdown voltage V_{CE} , thus improved output power characteristics and the ability to withstand large voltage swings to result in an improvement in device reliability and operational performance.

[0065] FIG. 1C illustrates a cross sectional view of an HBT having optional collector layers in accordance with the teachings of the present invention. An HBT transistor in accordance with the present invention can have one or more collector layers in order to achieve and realize an improve on-state breakdown voltage (V_{CE}) and thus, improved output power characteristics and improved ability to withstand large voltage swings, as discussed above in relation to FIGS. 1, 1A, and 1B. FIG. 1C illustrates the HBT **10C** can achieve the improved on-state breakdown voltage results discussed above, with at least two collector layers and optionally a third collector layer and if desired an optional fourth collector layer.

[0066] An HBT device having one collector layer in according with the teachings of the present invention is discussed below in more detail in relation to FIG. 3

[0067] The HBT **10C** is formed on a substrate and includes a collector region, a base region, an emitter region, and a contact region. The collector region of the HBT **10C** includes a sub-collector layer **14C**, a first collector layer **16C**, and a second collector layer **18C**. The collector region of the HBT **10C** can include a third collector layer **19C** and if desired a fourth collector layer **20C**. The base region of the HBT **10C** includes a base layer **22C**. In similar fashion, the emitter region of the HBT **10C** includes an emitter layer **24C**. The contact region of the HBT **10C** includes a first contact layer **26C** and a second contact layer **28C**. The HBT **10C** further includes an emitter electrode **34C** formed over a portion of the second contact layer **28C**, base electrodes **32G** and **32H** formed over portions of the base layer **22C**, and collector electrodes **30G** and **30H** formed over portions of the sub-collector layer **14C**.

[0068] In more detail, the sub-collector layer **14C** is a GaAs material formed over a GaAs substrate **12C**. The sub-collector layer **14C** has a thickness of about 400 nm with a donor impurity concentration of about $4 \times 10^{18} \text{ cm}^{-3}$.

[0069] The first collector layer **16C** is formed of a GaAs material over a portion of the sub-collector layer **14C**. The first collector layer **16C** can have a thickness range of between about 200 nm and about 400 nm. The first collector layer **16C** can have a donor impurity concentration of between about $7 \times 10^{16} \text{ cm}^{-3}$ and about $10 \times 10^{16} \text{ cm}^{-3}$.

[0070] The second collector layer **18C** is formed of a GaAs material over a portion of the first collector layer **16C**. The second collector layer **18C** has a thickness that can range from between about 200 nm to about 400 nm in 1 nm increments or decrements. The donor impurity concentration of the second collector layer **18C** can range between about $4 \times 10^{16} \text{ cm}^{-3}$ and about $7 \times 10^{16} \text{ cm}^{-3}$.

[0071] The third collector layer **19C** is formed of a GaAs material over a portion of the second collector layer **18C**. The third collector layer **19C** has a thickness of between about 100 nm and about 500 nm. The range of thicknesses can change in increments or decrements of 1 nm. The donor impurity concentration of the third collector layer **19C** can range between about $0.5 \times 10^{16} \text{ cm}^{-3}$ and about $4 \times 10^{16} \text{ cm}^{-3}$.

[0072] The fourth collector layer **20C** is formed of a GaAs material over a portion of the third collector layer **19C**. The fourth collector layer **20C** has a thickness of between about 100 nm and about 500 nm. The range of thicknesses can change in increments or decrements of 1 nm. The donor impurity concentration of the fourth collector layer **20C** can range between about $0.84 \times 10^{16} \text{ cm}^{-3}$ and about $4 \times 10^{16} \text{ cm}^{-3}$.

[0073] For the base layer **22C**, a P^+ type GaAs material is formed over a portion of either the second collector layer **18C**, the third collector layer **19C**, or the fourth collector layer **22C**, and is formed to have a thickness of about 100 nm. The base layer **22C** is doped to have an impurity concentration of between about $1 \times 10^{19} \text{ cm}^{-3}$ and about $5 \times 10^{19} \text{ cm}^{-3}$.

[0074] For the emitter layer **24C**, either an InGaP type material, an $\text{Al}_x\text{Ga}_{1-x}\text{As}$ where ($0 < x < 0.35$) type material, or a $(\text{Al}_x\text{Ga}_{1-x})_{0.49}\text{In}_{0.51}\text{P}$ where ($0 < x < 0.35$) type material is formed over a portion of the base layer **22C** to have a thickness of about 50 nm with a doping concentration between about $3 \times 10^{17} \text{ cm}^{-3}$ and about $10 \times 10^{17} \text{ cm}^{-3}$.

[0075] The first contact layer **26B** is formed of a GaAs material doped with N^+ type impurities to a concentration of about $4 \times 10^{18} \text{ cm}^{-3}$. The first contact layer **26B** is formed over a portion of the emitter layer **24B** and is formed to have a thickness of about 100 nm. The second contact layer **28B** is formed over a portion of the first contact layer **26B** of an $\text{In}_{0.5}\text{Ga}_{0.5}\text{As}$ material doped with N^+ type impurities in a concentration above $1 \times 10^{19} \text{ cm}^{-3}$.

[0076] The improvement in the on-state voltage breakdown V_{CE} in the above illustrative embodiments of the compound semiconductor device is accomplished by the insertion of a higher doped collector layer near the sub-collector layer to reduce the electric field at the junction of the collector and the sub-collector of the HBT **10C**. The introduction of collector layer having a donor impurity concentration of between about $7 \times 10^{16} \text{ cm}^{-3}$ and about $10 \times 10^{16} \text{ cm}^{-3}$ adjacent to a sub-collector layer reduces the electric field at the collector/sub-collector junction which avoids the occurrence of avalanche breakdown at this junction.

[0077] The electric field at the junction of a sub-collector layer and a collector layer is reduced from between about

6×10^4 V/cm to about 8×10^4 V/cm to a reduced level of between about 2×10^4 V/cm to about 3×10^4 V/cm. The reduction in the electric field results in an improvement of an on-state breakdown voltage V_{CE} value of between about 9V and about 10V at a collector current density of about 80 kA/cm². As a result, the HBT 10C is able to realize an improvement in on-state breakdown voltage V_{CE} , thus improved output power characteristics and the ability to withstand large voltage swings to result in an improvement in device reliability and operational performance.

[0078] FIG. 2 illustrates a cross-sectional view of an HBT according to another illustrative embodiment of the present invention. The HBT 50 is formed on a substrate and includes a collector region, a base region, an emitter region and a contact region. The collector region of the HBT 50 includes a sub-collector layer 54, a first collector layer 56, a second collector layer 58, and a third collector layer 60. The base region of the HBT 50 includes a base layer 62. The emitter region of the HBT 50 includes an emitter layer 64. In like manner, the contact region of the HBT 50 includes a first contact layer 66 and a second contact layer 68.

[0079] The HBT 50 further includes an emitter electrode 74 formed over a portion of the second contact layer 68, base electrodes 72A and 72B formed over portions of the base layer 62, and collector electrodes 70A and 70B formed over portions of the sub-collector layer 54.

[0080] In more detail, the substrate 52 is a GaAs material. The sub-collector layer 54 is a GaAs material formed over the substrate 52 and is formed to have a thickness of about 400 nm with a donor impurity concentration of 4×10^{18} cm⁻³. The first collector layer 56 is formed of an AlGaAs material with an Al concentration of between about 25% to about 35% and is formed to have a thickness of about 200 nm. The first collector layer 56 has an impurity concentration of between about 7×10^{16} cm⁻³ and about 10×10^{16} cm⁻³.

[0081] In like manner, the second collector layer 58 is formed of a GaAs material having a thickness of 200 nm and an impurity concentration of between about 4×10^{16} cm⁻³ and about 7×10^{16} cm⁻³. The second collector layer 58 is formed over a portion of the first collector layer 56. The third collector layer 60 is formed over a portion of the second collector layer 58 and is formed of a GaAs material. The third collector layer 60 has a thickness of about 400 nm and has a low impurity concentration of between about 0.5×10^{16} cm⁻³ and about 4×10^{16} cm⁻³.

[0082] For the base layer 62, a GaAs material is formed over a portion of the third collector layer 60 and is formed to have a thickness of 100 nm. The base layer 62 is doped to have a P⁺ acceptor impurity concentration of between about 1×10^{19} cm⁻³ and about 5×10^{19} cm⁻³.

[0083] For the emitter layer 64, an N⁺ type InGaP material is formed to a thickness of about 50 nm with a donor impurity concentration of about 3×10^{17} cm⁻³. The first contact layer 66 is formed over a portion of the emitter layer 64. The first contact layer 66 is formed of a GaAs material to a thickness of about 100 nm with an N⁺ donor impurity concentration of about 4×10^{18} cm⁻³. The second contact layer 68 is formed of an In_{0.5}Ga_{0.5}As material doped with N⁺ type impurities in a high concentration in excess of 1×10^{19} cm⁻³. The second contact layer 68 is formed to have a thickness of 100 nm.

[0084] The improvement in the on-state voltage breakdown V_{CE} in the above illustrative embodiment of the compound semiconductor device is accomplished by the insertion of a high composition AlGaAs near the sub-collector layer to

reduce the electric field at the junction of the collector and the sub-collector of the HBT 50. The introduction of collector layer having a high composition of AlGaAs adjacent a sub-collector layer reduces the electric field at the collector/sub-collector heterojunction, and hence reduces or suppresses the electric field near this junction.

[0085] A reduction in the electric field at the junction of a sub-collector layer and a collector layer from between about 6×10^4 V/cm and about 8×10^4 V/cm to a reduced level of between about 2×10^4 V/cm and about 3×10^4 V/cm is realized and results in an improvement of an on-state breakdown voltage V_{CE} value of between about 8V and about 10V at a collector current density of between about 60 kA/cm² and about 80 kA/cm². The high composition AlGaAs increases the bandgap of the collector region in the HBT 50 and as a consequence diminishes the saturation stored charged density of the device and speeds up device turnoff after the device is biased in the saturation region. As a result, the HBT 50 is able to realize an improvement in on-state breakdown voltage V_{CE} , thus improved output power characteristics, and the ability to withstand large voltage swings to result in an improvement in device reliability and operational performance.

[0086] FIG. 3 illustrates a cross sectional view of an HBT according to another illustrative embodiment of the present invention. The HBT 200 is formed with one collector layer having a graded doping concentration to achieve an improved on-state breakdown voltage (V_{CE}) and thus, improved output characteristics and improved ability to withstand large voltage swings, as discussed above in relation to FIGS. 1, 1A, 1B, 1C, and 2. The graded doping concentration of the collector layer in HBT 200 allows for the formation of a single collector layer as an alternative to formation of multiple collector layers as discussed above in relation to FIGS. 1, 1A, 1B, 1C, and 2, to achieve the reduced on-state breakdown voltage as taught by the present invention.

[0087] The HBT 200 is formed on a substrate and includes a collector region, a base region, an emitter region, and a contact region. The collector region of the HBT 200 includes a sub-collector layer 204 and a collector layer 206. The base region of the HBT 200 includes a base layer 208. In similar fashion, the emitter region of the HBT 200 includes an emitter layer 210. The contact region of the HBT 200 includes a first contact layer 212 and a second contact layer 214. The HBT 200 further includes an emitter electrode 220 formed over a portion of the second contact layer 214, base electrodes 218A and 218B formed over portions of the base layer 208, and collector electrodes 216A and 216B formed over portions of the sub-collector layer 204.

[0088] In more detail, the sub-collector layer 204 is a GaAs material formed over a GaAs substrate 202. The sub-collector layer 204 has a thickness of about 400 nm with a donor impurity concentration of about 4×10^{18} cm⁻³.

[0089] The collector layer 206 is formed of a GaAs material over a portion of the sub-collector layer 204. The collector layer 206 can have a thickness range of between about 200 nm and about 1000 nm and has a graded or ramped doping concentration.

[0090] The graded doping concentration of the collector layer 206 is carried out to achieve a doping concentration that increases in a downward direction from a first surface of the collector layer 206 adjacent the base layer 208 to a second surface of the collector layer 206 adjacent to a surface of the sub-collector layer 204. One suitable graded doping concen-

tration can range from between about $1 \times 10^{16} \text{ cm}^{-3}$ adjacent the first surface of the collector layer **206** and graded or ramped to increase in concentration of between about $7 \times 10^{16} \text{ cm}^{-3}$ to about $10 \times 10^{16} \text{ cm}^{-3}$ at the second surface of the collector **206** adjacent the surface of the sub-collector **204**. In one embodiment of the HBT **200** the doping concentration of the collector layer **206** at the second surface of the collector **206** adjacent the surface of the sub-collector **204** is about $8 \times 10^{16} \text{ cm}^{-3}$.

[0091] For the base layer **208**, a P⁺ type GaAs material is formed over a portion of the collector layer **206** and is formed to have a thickness of about 100 nm. The base layer **206** is doped to have an impurity concentration of between about $1 \times 10^{19} \text{ cm}^{-3}$ and about $5 \times 10^{19} \text{ cm}^{-3}$.

[0092] For the emitter layer **210**, either an InGaP type material, an $\text{Al}_x\text{Ga}_{1-x}\text{As}$ where $(0 < x < 0.35)$ type material, or a $(\text{Al}_x\text{Ga}_{1-x})_{0.49}\text{In}_{0.51}\text{P}$ where $(0 < x < 0.35)$ type material is formed over a portion of the base layer **208** to have a thickness of about 50 nm with a doping concentration between about $3 \times 10^{17} \text{ cm}^{-3}$ and about $10 \times 10^{17} \text{ cm}^{-3}$.

[0093] The first contact layer **212** is formed of a GaAs material doped with N⁺ type impurities to a concentration of about $4 \times 10^{18} \text{ cm}^{-3}$. The first contact layer **212** is formed over a portion of the emitter layer **210** and is formed to have a thickness of about 100 nm. The second contact layer **214** is formed over a portion of the first contact layer **212** of an $\text{In}_{0.5}\text{Ga}_{0.5}\text{As}$ material doped with N⁺ type impurities in a concentration above $1 \times 10^{19} \text{ cm}^{-3}$.

[0094] The improvement in the on-state voltage breakdown V_{CE} in the above illustrative embodiment of the compound semiconductor device is accomplished by the insertion of a higher doped collector layer near the sub-collector layer to reduce the electric field at the junction of the collector and the sub-collector of the HBT **200**. The introduction of collector layer having a donor impurity concentration of between about $7 \times 10^{16} \text{ cm}^{-3}$ and about $10 \times 10^{16} \text{ cm}^{-3}$ adjacent to a sub-collector layer reduces the electric field at the collector/sub-collector junction which avoids the occurrence of avalanche breakdown at this junction.

[0095] The electric field at the junction of a sub-collector layer and a collector layer is reduced from between about $6 \times 10^4 \text{ V/cm}$ to about $8 \times 10^4 \text{ V/cm}$ to a reduced level of between about $2 \times 10^4 \text{ V/cm}$ to about $3 \times 10^4 \text{ V/cm}$. The reduction in the electric field results in an improvement of an on-state breakdown voltage V_{CE} value of between about 9V and about 10V at a collector current density of about 80 kA/cm^2 . The high donor impurity concentration adjacent the sub-collector layer increases the bandgap of the collector region in the HBT **200**, diminishes the saturation stored charged density of the device, and speeds up device turnoff after the device is biased in the saturation region. As a result, the HBT **200** is able to realize an improvement in on-state breakdown voltage V_{CE} , thus improved output power characteristics and the ability to withstand large voltage swings to result in an improvement in device reliability and operational performance.

[0096] FIG. 4 illustrate the steps taken to form one of the illustrative compound semiconductor devices of the present invention. On a provided substrate (step **100**) a collector region is formed having at least one layer to form a first stack (step **102**). Suitable techniques for forming the collector region include metal organic chemical vapor deposition (MOCVD) or molecular beam epitaxy (MBE). Upon formation of the collective region, a base region is formed or grown

over a portion of the collector region (step **104**). The base region is formed to include at least one layer and forms a second stack. An emitter region is grown or formed over a portion of the base region to form a third stack (step **106**). The emitter region is formed to have at least one layer. In similar fashion, a contact region is grown or formed over a portion of the emitter region to form a fourth stack (step **108**). The contact region is formed to have at least one layer. The emitter electrode, the base electrodes, and the collector electrodes are formed by metal deposition and liftoff, self-aligned or non-self-aligned, using a material of Ti, Au, Ni, W, Ge, Pt. (step **110**). Those skilled in the art will recognize that each of the stacks discussed above are capable of being formed by MOCVD or by MBE. Nonetheless, those skilled in the art will recognize that other fabrication methods may be suitable depending on feature sizes or other constraints such as material type.

[0097] FIG. 5 graphically illustrates the improvement in the on-state breakdown voltage (V_{CE}) and thus, improved output power characteristics and improved ability to withstand large voltage swings of an HBT device according to the teachings of the present invention. Graph 410 graphically depicts the measured results of four HBT devices having a reduced electric field near the collector/subcollector junction as a result of a high donor impurity concentration of the collector region adjacent the sub-collector layer to increase the bandgap of the collector region of an HBT device. Graph 410 plots current density J_C versus on-state breakdown voltage V_{CE} for four HBT devices. HBT device labeled InGaP refers to a conventional HBT device having a subcollector layer with a thickness of about 500 nm and a doping concentration of about $4 \times 10^{18} \text{ cm}^{-3}$ and a single collector layer formed of GaAs having a thickness of about 10000 nm with a doping concentration of about $1 \times 10^{16} \text{ cm}^{-3}$. The HBT device labeled Collector-1 in graph 410 represents an HBT device according to FIG. 1. The HBT device labeled Collector 2 in graph 410 represents an HBT device depicted by any of FIGS. 1, 1A, and 1B. The HBT device labeled Collector-3 of graph 410 represents an HBT device having four collector layers as illustrated in FIG. 1C. The HBT device labeled Collector-AlGaAs of FIG. 410 represents results of an HBT having a structure similar to HBT **50** of FIG. 2.

[0098] FIG. 410 graphically illustrates that the on-state breakdown voltage V_{CE} of the conventional (InGaP) HBT device has an on-state breakdown voltage between six and seven volts when the current density J_C reaches about 80 kA/cm^2 . Contrary to the conventional HBT, HBT devices according to the teachings of the present invention are able to improve the on-state breakdown voltage V_{CE} performance at high current densities. For example, at a current density of about 80 kA/cm^2 the devices labeled Collector 1-3 and Collector-AlGaAs resulted in on-state breakdown voltages that range between about 9V about 10V while the conventional InGaP HBT device realized an on-state breakdown voltage of about 6.5 V.

[0099] Those skilled in art will appreciate that the applications of the various compound semiconductor devices described herein are not limited solely to terrestrial based digital communications, for example, the compound semiconductor devices of the present invention are well suited for operation in portable or mobile electronic devices capable of communicating with a satellite network in a wireless manner or a hybrid network of terrestrial network entities and satellite network entities.

[0100] While the present invention has been described with reference to illustrative embodiments thereof, those skilled in the art will appreciate that various changes in form in detail may be made without parting from the intended scope of the present invention as defined in the appended claims.

What is claimed:

1. A heterojunction bipolar transistor, comprising
a substrate;
a collector region having a plurality of layers formed of a first material and a layer of a second material;
a base region having at least one layer formed of said first material;
an emitter region having at least one layer formed of a third material; and
a contact region having a first layer formed of said first material and a second layer of a fourth material;
wherein the collector region reduces an electric field adjacent to two adjacent layers of the plurality of layers of said collector region to improve a drain-source on-state breakdown voltage of the heterojunction bipolar transistor.
2. The heterojunction bipolar transistor of claim 1, wherein the first material comprises GaAs.
3. The heterojunction bipolar transistor of claim 1, wherein the second material comprises AlGaAs.
4. The heterojunction bipolar transistor of claim 1, wherein the third material comprises InGaP.
5. The heterojunction bipolar transistor of claim 1, wherein the fourth material comprises $\text{In}_{0.5}\text{Ga}_{0.5}\text{As}$.
6. The heterojunction bipolar transistor of claim 1, wherein the plurality of layers of the first material of the collector region comprises,
a sub-collector layer of the first material;
a first collector layer of the first material; and
a second collector layer of the first material.
7. The heterojunction bipolar transistor of claim 6, wherein the first collector layer of the first material has a thickness of between about 200 nm and about 400 nm.
8. The heterojunction bipolar transistor of claim 6, wherein the second collector layer of the first material has a thickness of between about 200 nm and about 400 nm.
9. The heterojunction bipolar transistor of claim 6, wherein the sub-collector layer has a thickness of between about 100 nm and about 500 nm.

10. The heterojunction bipolar transistor of claim 6, wherein in the collector region the layer of the second material of has a thickness of about 200 nm.

11. The heterojunction bipolar transistor of claim 6, wherein the substrate comprises a semi-insulating material.

12. The heterojunction bipolar transistor of claim 1, wherein the layer of the second material has an impurity concentration different from one of the plurality of layers of the first material.

13. A heterojunction bipolar transistor, comprising
a substrate;

a collector region having a first layer formed of a first material and at least a second layer formed of the first material, the second layer having a gradually varied doping concentration from a first surface to a second surface of the second layer;

a base region having at least one layer formed of said first material;

an emitter region having at least one layer formed of a second material; and

a contact region having a first layer formed of said first material and a second layer formed of a third material;
wherein the collector region reduces an electric field adjacent to a first surface of the first layer of the first material and a first surface of the second layer of the first material to improve a drain source on-state breakdown voltage of the heterojunction bipolar transistor.

14. The heterojunction bipolar transistor of claim 13, wherein the first material comprises GaAs.

15. The heterojunction bipolar transistor of claim 13, wherein the doping concentration of the at least second layer of the first material forming a portion of the collector region increases in concentration from the first surface of the second layer adjacent a surface of the base region to the second surface of the second layer adjacent a first surface of the first layer of collector region.

16. The heterojunction bipolar transistor of claim 13, wherein the first layer of the first material of the collector region comprises, a sub-collector layer of the first material.

17. The heterojunction bipolar transistor of claim 13, wherein the second layer of the first material of the collector region comprises, a collector layer of the first material.

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